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UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1752**

Serial No.: **10/629,806**

Examiner: **LEE, SIN J**

Filed: **July 30, 2003**

Confirmation No.: **9494**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR
FORMING RESIST PATTERN, AND PROCESS FOR MANUFACTURING
SEMICONDUCTOR DEVICE**

Attorney Docket No.: **030923**

Customer Number: **38834**

AMENDMENT UNDER 37 CFR §1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

September 2, 2004

Sir:

In response to the Office Action dated June 3, 2004, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 8 of this paper.